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(51) International Patent Classification 6 : G06T 7/00	A1	(11) International Publication Number: WO 97/36260 (43) International Publication Date: 2 October 1997 (02.10.97)
(21) International Application Number: PCT/CA97/00196 (22) International Filing Date: 25 March 1997 (25.03.97) (30) Priority Data: 08/622,193 25 March 1996 (25.03.96) US (71) Applicant: FOCUS AUTOMATION SYSTEMS INC. [CA/CA]; 101 Randall Drive, Waterloo, Ontario N2V 1C5 (CA). (72) Inventors: PEARSON, Eric, Clifford; 3 Weberlyn Crescent, Conestoga, Ontario N0B 1N0 (CA). MCCLOY, Bradley, John; R.R. #1, New Dundee, Ontario N0B 2E0 (CA). BURJOSKI, Joseph, Daniel; 689 Glen Forest Boulevard, Waterloo, Ontario N2L 4K7 (CA). (74) Agents: IMAI, Jeffrey, T. et al.; Gowling, Strathy & Henderson, Suite 4900, Commerce Court West, Toronto, Ontario M5L 1J3 (CA).		(81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CU, CZ, DE, DK, EE, ES, FI, GB, GE, HU, IL, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN, ARIPO patent (GH, KE, LS, MW, SD, SZ, UG), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG). Published <i>With international search report.</i>
(54) Title: METHOD, APPARATUS AND SYSTEM FOR VERIFICATION OF PATTERNS (57) Abstract A method, apparatus and system for verifying the establishment of a pattern includes means for storing a template of the pattern, means for acquiring an image of the established pattern, a first image processing means to alter at least one of said template and acquired images to produce at least two resultant images, comparison means to compare the two resultant images with the other of said template and acquired image and means to evaluate the results of each comparison to determine if the established pattern includes a defect. Both gray scale and binary processing and comparisons are disclosed for use as required.		



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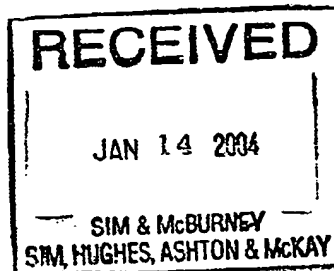
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January 9, 2004



Application No. : **2,317,803**
Owner : **SAMSUNG ELECTRONICS CO., LTD.**
Title : **METHOD FOR INSPECTING INFERIORITY IN SHAPE**
Classification : **G01N-21/88**
Your File No. : **8590-15 DAR/ds**
Examiner : **Wendy Stewart**

YOU ARE HEREBY NOTIFIED OF :

- A REQUISITION BY THE EXAMINER IN ACCORDANCE WITH SUBSECTION 30(2) OF THE *PATENT RULES*;
- A REQUISITION BY THE EXAMINER IN ACCORDANCE WITH SECTION 29 OF THE *PATENT RULES*.

IN ORDER TO AVOID MULTIPLE ABANDONMENTS UNDER PARAGRAPH 73(1)(A) OF THE *PATENT ACT*, A WRITTEN REPLY TO EACH REQUISITION MUST BE RECEIVED WITHIN 6 MONTHS AFTER THE ABOVE DATE.

This application has been examined taking into account applicant's correspondence received in this office on January 26, 2001 and May 29, 2001.

The number of claims in this application is 7, dated Jan. 26, 2001.

The examiner has identified the following defects in the application:

A search of the prior art has revealed the following:

References Applied:

United States Patent

5 333 093

Aug. 16, 1994

G09G 3/36

Kumagai et al.

Canadian Patent

2 249 265

Oct. 2, 1997

G06T 7/00

Pearson et al.